

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
ASMMC.008AUSAPPLICATION NO.
08/452,844INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT
Realmakers et al.FILING DATE
December 3, 1999GROUP
2825

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
RM	1	6,270,572	08/07/01	Kim et al.	—	—	
RM	2	6,335,240	01/01/02	Kim et al.	—	—	
RM	3	5,923,056	07/13/99	Lee et al.	—	—	
RM	4	6,342,712	01/29/02	Miki et al.	—	—	

EXAMINER
INITIAL

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

RM	5	Materro et al., "Effect of water dose on the atomic layer deposition rate of oxide thin films." Thin Solid Films 368 (2000), pgs. 1-7					
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081303RECEIVED
AUG 20 2003
TECHNOLOGY CENTER 2800

EXAMINER

DeWitt N. Reutimann

DATE CONSIDERED

10/20/2003

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